Amendments to the Specification:

Please amend paragraphs **[0047]** and **[0082]**, as shown below.

[0047] Figure 2 depicts a state-of-the-art scatterometer. The scatterometer includes a light source 1, which directs a light beam 2 towards a structure 5, generally some type of grating, on a substrate ~~W~~ 3 to be exposed, lying on a substrate table ~~WT~~ 6, and a detector 4. The detector 4 is connected to a (micro)processor 9, which is connected to a memory 10. The light beam 2 reflects and/or diffracts at the suitable structure 5 positioned on the surface of the substrate ~~W~~ 3. The spectrum of the reflected light beam is detected by the detector 4. The light beam 2 may be directed towards the substrate ~~W~~ 3 at an angle, as shown in figure 2, but may also be directed perpendicular to the substrate ~~W~~ 3. There are several scatterometry concepts, in which one or more sets of properties of the light, which is directed to the suitable structure, can be varied simultaneously. Examples of a set of properties are a set of wavelengths, a set of angles of incidence, a set of polarization states or a set of phases and/or phase differences. The detector can be arranged to detect one or a combination of the aforementioned sets, and may include one or more sensors to record different parts of the reflected and/or diffracted light.

[0082] Finally the processor 9 supplies 914 the derived values of these parameters to the lithographic apparatus 901. The lithographic apparatus 901 may use, for example, the derived values to monitor the drifts within the apparatus with respect to a reference state. The derived values are then used in feedback signals to correct for these drifts. In this case, the lithographic apparatus 901 is provided with a correction control unit, which uses the applied correction signals to compensate for drift. That correction control unit 903 may be configured to control, for example, the height of the substrate table WT to improve focus.